

PHOTOLITHOGRAPHY SYSTEM WITH VARIABLE SHUTTER AND METHOD OF USING THE SAME

Abstract

A photolithography system applied to the semiconductor process includes a light source, a shutter set, and a lens set. The shutter set has a variable opening area. The shutter set can include a plurality of triple-blade shutters and utilizes step motors to adjust the relative positions of the triple-blade shutters. The opening area is adjusted in accordance with the intensity of the light source or the required dose.